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APPLICATION NO.	NO. FILING DATE		FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
09/895,678	-	06/29/2001	John Stephen Drewery	NOVEP008	6878
25920	7590	08/11/2003			•
MARTINI		•	EXAMINER		
710 LAKES		_	CULBERT, ROBERTS P		
SUNNYVALE, CA 94085				ART UNIT	PAPER NUMBER
				1763	
			DATE MAILED: 08/11/2003		

Please find below and/or attached an Office communication concerning this application or proceeding.

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Application No.	Applicant(s)
09/895,678	DREWERY, JOHN STEPHEN
Examiner	 Art Unit
Roberts Culbert	1763

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --

THE REPLY FILED 02 July 2003 FAILS TO PLACE THIS APPLICATION IN CONDITION FOR ALLOWANCE. Therefore, further action by the applicant is required to avoid abandonment of this application. A proper reply to a final rejection under 37 CFR 1.113 may only be either: (1) a timely filed amendment which places the application in condition for allowance; (2) a timely filed Notice of Appeal (with appeal fee); or (3) a timely filed Request for Continued Examination (RCE) in compliance with 37 CFR 1.114.

U.S. Patent and Trademark Office PTO-303 (Rev. 04-01) Continuation of 5. does NOT place the application in condition for allowance because:

Applicant has argued on Page 2 of remarks that Lu does not disclose all the features of the claimed invention. The argument is not persuasive because the Lu reference does teach all the features of the claimed invention including the release layer. As in the prior art, the terms relase layer and sacrificial layer are interpreted broadly as a layer or material region that separates two other layers or regions and facilitates the separation of the two other layers or regions based on the materials of construction. The terms "sacrificial layer" and "release layer" do not indicate what type of process is used to remove the material in the separation.

Applicant has argued on Page 3 of remarks that CMP is mainly a mechanical process. The argument is not persuasive because it is

generally accepted that CMP involves a chemical dissolving assisted by mechanical abrasion.

Applicant has argued on Page 3 of remarks that the process of Lu is not a chemical dissolving process because the layer 102 of Lu would be dissolved away as well. The argument is not persuasive because in Lu the sacrificial layer is separated from the layer 102 by a polish stop layer made from SiC.

Applicant has argued on Page 4 of remarks that the sacrificial layer of Lu is not the same as the photosensitive release layer of the claimed invention. The argument is not persuasive because the sacrificial layer of Lu may be a photosensitive dielectric. See paragraph 12 of Lu.

Application/Control Number: 09/895,678

Art Unit: 1763

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should

be directed to Roberts Culbert whose telephone number is (703) 305-7965. The examiner can normally

be reached on Monday-Friday (7:30-4:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor,

Gregory Mills can be reached on (703) 308-1633. The fax phone numbers for the organization where this

application or proceeding is assigned are (703) 872-9310 for regular communications and (703) 872-9311

for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be

directed to the receptionist whose telephone number is (703) 308-0661.

R. Culbert

August 5, 2003